r 	*** ** - T	Search Text	DB `	Time stamp
L Number	Hits 27606	((low near10 dielectric) (organo near3	USPAT;	2003/04/02 15:57
1	27806	silic\$5 near3 glass))	US-PGPUB	
2	1300	(((low near10 dielectric) (organo near3	USPAT;	2003/04/02 15:51
2	1000	silic\$5 near3 glass))) and (plasma near10	US-PGPUB	
		(treat\$6))		2002/04/02 15:52
3	2539	(((low near10 dielectric) (organo near3	USPAT;	2003/04/02 15:52
_		silic\$5 near3 glass))) and (reduc\$3 near5	US-PGPUB	
		(agent gas plasma))	USPAT;	2003/04/02 15:20
4	3454	((((low near10 dielectric) (organo near3	US-PGPUB	2003/01/02 10:10
		<pre>silic\$5 near3 glass))) and (plasma near10 (treat\$6))) ((((low near10 dielectric)</pre>	05 TGLOD	
		(treat(6))) ((((low hear)) dielectic) (organo near3 silic\$5 near3 glass))) and	1	
	1	(reduc\$3 near5 (agent gas plasma)))		
_	2106	(((((low near10 dielectric) (organo near3	USPAT;	2003/04/02 15:58
5	2100	silic\$5 near3 glass))) and (plasma near10	US-PGPUB	ļ
		(treat\$6))) ((((low near10 dielectric)		
		(organo near3 silic\$5 near3 glass))) and		
		(reduc\$3 near5 (agent gas plasma)))) and		
		(hydrogen "H.sub.2" and (argon Ar nitrogen		
		"N.sub.2"))	rianam.	2003/04/02 15:23
6	1848	((((((low near10 dielectric) (organo near3	USPAT; US-PGPUB	2003/04/02 13.23
}		silic\$5 near3 glass))) and (plasma near10	US-PGPUB	
		<pre>(treat\$6))) ((((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and</pre>		
		(reduc\$3 near5 (agent gas plasma)))) and	1	
		(hydrogen "H.sub.2" and (argon Ar nitrogen	1	
	1	"N.sub.2"))) and (via trench hole open\$4)		
7	361	(((((((low near10 dielectric) (organo	USPAT;	2003/04/02 15:53
'	301	near3 silic\$5 near3 glass))) and (plasma	US-PGPUB	
		near10 (treat\$6))) ((((low near10		
		dielectric) (organo near3 silic\$5 near3		
		glass))) and (reduc\$3 near5 (agent gas		
		plasma)))) and (hydrogen "H.sub.2" and		
		(argon Ar nitrogen "N.sub.2"))) and (via		
		trench hole open\$4)) and (wet near8		
	206	(treat\$3 etch\$3 clean\$3)) ((((((((low near10 dielectric) (organo	USPAT;	2003/04/02 15:55
8	206	near3 silic\$5 near3 glass))) and (plasma	US-PGPUB	
.]		near10 (treat\$6))) (((low near10		
		dielectric) (organo near3 silic\$5 near3		
		glass))) and (reduc\$3 near5 (agent gas		
		plasma)))) and (hydrogen "H.sub.2" and	Ì	
		(argon Ar nitrogen "N.sub.2"))) and (via		
		trench hole open\$4)) and (wet near8		
	ļ	(treat\$3 etch\$3 clean\$3))) and (HF		·
		(hydrogen near3 fluoride) (hydro near3 fluoric near3 acid) (sulfuric near3 acid)		
		("H.sub.2" adj "SO.sub4") ((citric acetic		
		oxallic) near5 acid))		
9	17236	((low near10 dielectric) (organo near3	EPO; JPO;	2003/04/02 15:51
1		silic\$5 near3 glass))	DERWENT;	
	-		IBM_TDB	2002/04/02 15:52
10	123	(((low near10 dielectric) (organo near3	EPO; JPO;	2003/04/02 15:52
		silic\$5 near3 glass))) and (plasma near10	DERWENT;	
		(treat\$6))	IBM_TDB EPO; JPO;	2003/04/02 15:52
11	123	(((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (reduc\$3 near5	DERWENT;	2003/04/02 13:32
1			IBM TDB	
12	235	(agent gas plasma)) ((((low near10 dielectric) (organo near3	EPO; JPO;	2003/04/02 15:52
12	235	silic\$5 near3 glass))) and (plasma near10	DERWENT;	
		(treat\$6))) (((low near10 dielectric)	IBM TDB	
	ļ	(organo near3 silic\$5 near3 glass))) and	_	,
		(reduc\$3 near5 (agent gas plasma)))		
13	34	(((((low near10 dielectric) (organo near3	EPO; JPO;	2003/04/02 15:52
		silic\$5 near3 glass))) and (plasma near10	DERWENT;	
		(treat\$6))) ((((low near10 dielectric)	IBM_TDB	
		(organo near3 silic\$5 near3 glass))) and		
		(reduc\$3 near5 (agent gas plasma)))) and (hydrogen "H.sub.2" and (argon Ar nitrogen		
		(hydrogen "H.sub.2" and (argon Ar hittiogen "N.sub.2"))		
L		N.3UD.2 11		

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14	2	((((((low near10 dielectric) (organo near3	EPO; JPO;	2003/04/02 15:53
11		silic\$5 near3 glass))) and (plasma near10	DERWENT;	
	1	(treat\$6))) ((((low near10 dielectric)	IBM_TDB	
		(organo near3 silic\$5 near3 glass))) and		
		(reduc\$3 near5 (agent gas plasma)))) and		
		(hydrogen "H.sub.2" and (argon Ar nitrogen		
		"N.sub.2"))) and (wet near8 (treat\$3		
		etch\$3 clean\$3))	EPO; JPO;	2003/04/02 15:58
15	2	(((((low near10 dielectric) (organo near3	DERWENT;	2003/04/02 13:30
		silic\$5 near3 glass))) and (plasma near10	IBM TDB	
		(treat\$6))) ((((low near10 dielectric)	1014_100	:
		(organo near3 silic\$5 near3 glass))) and (reduc\$3 near5 (agent gas plasma)))) and		
	i	(hydrogen "H.sub.2" and (argon Ar nitrogen		•
		"N.sub.2"))) and (HF (hydrogen near3		
		fluoride) (hydro near3 fluoric near3 acid)		
1	Ì	(sulfuric near3 acid) ("H.sub.2" adj		'
		"SO.sub4") ((citric acetic oxallic) near5		
		acid))		
16	4772	(damascene (dual near3 damascene))	USPAT;	2003/04/02 15:57
10			US-PGPUB	
17	779	((damascene (dual near3 damascene))) and	USPAT;	2003/04/02 15:58
		(((low near10 dielectric) (organo near3	US-PGPUB	
		silic\$5 near3 glass)) same plasma)		0000/04/00 15:50
18	543	(((damascene (dual near3 damascene))) and	USPAT;	2003/04/02 15:58
		(((low near10 dielectric) (organo near3	US-PGPUB	
		silic\$5 near3 glass)) same plasma)) and		
		(hydrogen "H.sub.2" and (argon Ar nitrogen		
ļ		"N.sub.2"))	USPAT;	2003/04/02 15:59
19	162	((((damascene (dual near3 damascene))) and	US-PGPUB	2003/04/02 13:33
		(((low near10 dielectric) (organo near3	US-FGFUD	
		silic\$5 near3 glass)) same plasma)) and		
		(hydrogen "H.sub.2" and (argon Ar nitrogen		
		"N.sub.2"))) and (HF (hydrogen near3 fluoride) (hydro near3 fluoric near3 acid)		
		(sulfuric near3 acid) ("H.sub.2" adj		
		"SO.sub4") ((citric acetic oxallic) near5		
		acid))		
	1	lacio))	·	I

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